



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Sujit Sharan and Gurtej S. Sandhu

Serial No.: 09/825,613

Filed: April 3, 2001

For: METHOD FOR PECVD DEPOSITION OF SELECTED  
MATERIAL FILMS

§  
§ Group Art Unit: 2829  
§  
§ Examiner: Lisa A Kilday  
§  
§ Atty. Docket: 95-0716.03  
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§  
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§

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SECOND AMENDMENT AND RESPONSE TO THE  
OFFICE ACTION OF SEPTEMBER 12, 2002

Certificate of Mailing (37 C.F.R. § 1.8)

Commissioner for Patents

Washington, D.C. 20231

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on the date below:

1/13/3  
Date

Charles Brantley  
Signature

Dear Sir:

Applicants herein respond to the Office Action of September 12, 2002. Please amend the above-captioned application as follows.

IN THE CLAIMS:

Please amend the claim to the form indicated below.

1. (Thrice amended) A process of PECVD deposition comprising the steps of:  
providing an ion promoting atmosphere; and  
contacting a substrate with a plasma of approximately 50 to 90 % of a metal-containing gas in said ion promoting atmosphere.